

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S134	4	(hafnium near2 nitride) with (gate electrode) and (nitrogen near10 hafnium near10 (ratio percent\$3))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 11:01
S135	4	(hafnium near2 nitride "hf. N") with (gate electrode) and (nitrogen near10 hafnium near10 (ratio percent\$3))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 12:57
S136	13	(hafnium near2 nitride "hf. N") with (gate electrode) and (((("N.sub.2") or nitrogen) with hafnium) with (ratio atom\$3 percent\$5))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 12:59
S138	161	(hafnium near2 nitride "hf.N" "Hf.N.sub.") near10 (gate electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:03
S137	161	(hafnium near2 nitride "hf. N") near10 (gate electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:03
S139	415	(hafnium and nitride) with (ratio percent\$5 "%")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:04
S141	170	S139 and S140	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:05
S140	646	((hafnium and (nitrogen ("N. sub."))) with (ratio percent\$5 "%"))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:05

S142	961	((hafnium and (nitrogen ("N.sub."))) with (ratio percent\$5 "%")) or ("Hf.sub.3")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:12
S143	7	S142 and (hafnium near2 nitride) with (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:13
S144	2587	(hafnium near2 nitride) or ("Hf.sub.3" "Hf.sub." "Hf.sub.N") with (ration atom\$3 percent\$5 "%")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:15
S146	68	S144 and S145	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:16
S145	68	(hafnium near2 nitride) with (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:16
S148	68	S147 and S145	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:18
S147	2590	(hafnium near2 nitride) or ("Hf.sub.3" "Hf.sub." "Hf.sub.N") with (ratio atom\$3 percent\$5 "%")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:18
S149	42	("Hf.sub.3N.sub.4")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:21
S150	92	("Hf.sub.3N.sub.4" "HfN.sub.x")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:24

S151	1	("Hf.sub.3N.sub.4" "HfN.sub.x") and (nitrogen near2 ratio near2 "Hf")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:27
S152	25	("Hf.sub.3N.sub.4" "HfN.sub.x") and (nitrogen near6 (hafnium "Hf") )	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:28
S153	12	("HfN.sub.x") and (nitrogen near6 (hafnium "Hf") )	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:30
S154	14	("HfN.sub.x") and (("N.sub.2" nitrogen) near6 (hafnium "Hf") )	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:32
S155	10	(metal near2 (gate electrode)) and (("N.sub.2" nitrogen) near6 (hafnium "Hf")) and (hafnium near2 nitride) near5 (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:34
S156	44	(hafnium near2 nitride "Hf.sub." "Hf.sub.N") near10 (gate adj electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:38
S157	5	(hafnium near2 nitride) near5 (cap\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 13:43
S158	364	(hafnium near2 nitride) and CMOS	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:06
S160	175	S159 and (@ad< "20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:12

S159	498	(hafnium near2 nitride "HfN") and (CMOS)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:12
S161	488691	((("438") or ("257")).CLAS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/03/26 14:53
S165	369	S164 and (@ad< "20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:54
S164	854	(hafnium near2 nitride) and S161	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:54
S163	0	(hafnium near2 nitride "HfN") with (caping near2 layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:54
S168	257	S167 and (@ad< "20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:56
S167	742	S164 not S160	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 14:56
S169	9	("HfN.sub." hafnium near2 nitride) with (gate near2 electrode) and (@ad< "20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:12
S170	69	("HfN.sub.x" hafnium near2 nitride) with (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:13

S171	68	("HfN.sub" hafnium near2 nitride) with (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:17
S172	1535	(hafnium Hf) with (gas precursor) and (nitride "N.sub.2") and (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:22
S174	636	S173 and (@ad< "20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:23
S173	1222	(hafnium Hf) with (gas precursor) and (nitrogen "N.sub.2") and (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:23
S176	148	S175 and (@ad< "20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:24
S175	296	(hafnium Hf) with (gas precursor) with (nitrogen "N.sub.2") and (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:24
S177	372	(hafnium near2 nitride) and (hafnium and nitrogen "N.sub.2") and (gate near2 electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:35
S178	141	S177 and (@ad< "20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 16:36
S179	265	(hafnium adj nitride HfN\$3) same (gate electrode) and (nitrogen "N.sub.2" "N:Hf" "Hf:N") and (ratio pertentct\$5 "%")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:17

S180	63	(hafnium adj nitride HfN\$3) same (gate electrode) and (nitrogen "N.sub.2" "N:Hf" "Hf:N") with (ratio pertentct\$5 "%")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:19
S181	2	("6,225,168").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/03/26 17:22
S182	66	(hafnium adj nitride HfN\$3) same (gate electrode) and (nitrogen "N.sub.2" "N:Hf" "Hf:N" "Hf/N" "N/Hf") with (ratio pertentct\$5 "%")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:31
S183	3	S182 not S180	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:36
S185	3028	(nitrogen "N.sub.2" "N:Hf" "Hf:N") with (ratio pertentct\$5 "%") and (gate adj electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:37
S184	79	(hafnium adj nitride HfN\$3) and (nitrogen "N.sub.2" "N:Hf" "Hf:N") with (ratio pertentct\$5 "%") and (gate adj electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:37
S188	141	S187 and (hafnium near2 nitride "HfN")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:38
S187	10500	S186 and (@ad<"20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:38
S186	14846	(gate electrode) and (nitrogen "N.sub.2" "N:Hf" "Hf:N" "Hf/N" "N/Hf") with (ratio pertentct\$5 "%")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/26 17:38

L2	1571	1 and (@ad<"20040317")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 10:51
L1	2372	(hafnium near2 nitride "HfN") near20 (metal "TiN" "TaN")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 10:51
L4	817	2 and (gate electrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 10:52
L3	0	2 and (gate near2 eletrode)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 10:52
L5	2	("7019351").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/03/27 12:58

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